

Notice of References Cited	Application/Control No. 10/596,373		Applicant(s)/Patent Under Reexamination TAM ET AL.	
	Examiner KENNY A. CESE		Art Unit 4174	Page 1 of 1

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
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*	B	US-2003/0021463	01-2003	Yamaguchi et al.	382/145
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	M	US-			

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NON-PATENT DOCUMENTS

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	V	Leunissen et al., "Line edge roughness: experimental results related to a two-parameter model", March 2004, Micro and Nano Engineering, Vol 73-74, pages 265-270
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.